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PATENT APPLICATION

Attorney Docket No.: 105875

AMENDMENT TRANSMITTAL

In re the Application of

Masaru MITSUI et al.

Application No.: 09/509,472

Group Art Unit: 1752

Examiner: Y. Clarke

Filed: April 21, 2000

For: PHOTOMASK BLANK, PHOTOMASK, METHODS OF MANUFACTURING THE SAME AND
METHOD OF FORMING MICROPATTERN

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Transmitted herewith is an Amendment in the above-identified application.

- ☐ Entitlement to small entity status is hereby asserted.
☐ Small entity status of this application has been established.

The filing fee has been calculated as shown below:

	(Column 1)	(Column 2)	(Column 3)
	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST NO. PREVIOUSLY PAID FOR	PRESENT EXTRA
TOTAL CLAIMS	*36 MINUS	**30	=6
INDEP CLAIMS	*5 MINUS	***5	=0
<input type="checkbox"/> FIRST PRESENTATION OF MULTIPLE DEP. CLAIM			

**SMALL
ENTITY**

RATE	ADD'L FEE
x 9	\$
x 42	\$
+ 140	\$
	\$

**OTHER THAN A
SMALL ENTITY**

RATE	ADD'L FEE
x 18	\$108
x 84	\$
+ 280	\$
	\$108

OR

OR

- * If the entry in Column 1 is less than the entry in Column 2, write "0" in Column 3.
** If the "Highest Number Previously Paid For" IN THIS SPACE is less than 20, write "20" in this space.
*** If the "Highest Number Previously Paid For" IN THIS SPACE is less than 3, write "3" in this space.

The "Highest Number Previously Paid For" in this space (Total or Independent) is the highest number found from the equivalent box in Column 1 of a prior Amendment or the number of claims originally filed.

- ☒ Check No. 137814 in the amount of \$108 is attached. The Director is hereby authorized to charge any other fees that may be required to complete this filing, or to credit any overpayment, to Deposit Account No. 15-0461. Two duplicate copies of this sheet are attached.

DEPOSIT ACCOUNT USE
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Please grant any extension
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Respectfully submitted,

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JAO:JSA:CWB/rxg

Date: January 2, 2003

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JCT 1700 MAIL ROOM



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Docket No.: 105875

19/D

PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Prior to further examination of the above-identified application, please amend the application as follows:

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IN THE CLAIMS:

Please cancel claims 1-30 without prejudice to or disclaimer of the subject matter contained therein.

Please add new claims 31-66 as follows:

31. A photomask blank forming a thin film having a shading function and containing one or more transition metals or compounds thereof on a transparent substrate, wherein the thin film restrains a film stress to be small by containing He, and wherein the content of He in the thin film is in a range of a film stress that the amount of change in flatness degree expressed by the difference in flatness degree between an initial value of the flatness degree which is the flatness degree of the transparent substrate when the